ABSTRACT

The present invention provides a process for producing a polishing slurry, which achieves high-speed polishing of a principal plane of a glass substrate even when ceria crystal fine particles or ceria-zirconia solid solution crystal fine particles are employed.

A process for producing a polishing slurry having a pH of from 2 to 7, comprising preparing a polishing slurry liquid containing abrasive particles, a dispersing agent and water, wherein the abrasive particles comprise ceria particles or ceria-zirconia solid solution particles and the dispersing agent comprises 2-pyridine carboxylic acid or glutamic acid; dispersing the abrasive particles of the polishing slurry liquid so that the reduction ratio of the crystallite diameter of the abrasive particles becomes at most 10%; subsequently adding water; and adding the same dispersing agent as the above dispersing agent.